ABSTRACT

METHOD AND APPARATUS FOR TREATING SUBSTRATES

The application describes several methods and an apparatus for treatment of at least partial areas of a substrate. In said methods, at least one liquid is applied to at least one partial area of the substrate and electromagnetic radiation is introduced into this liquid, in order to achieve a desired effect in accordance with the respective method. In one method, radicals are generated in the liquid by means of UV radiation prior to application of the liquid, wherein generation of the radicals occurs directly before applying the liquid to the substrate. In one method, electromagnetic radiation is introduced into said liquid such that at least a portion of the radiation reaches the substrate surface. In another method, UV radiation of a predetermined range of wavelength is guided through said liquid onto at least the partial area of the surface of said substrate. The methods may be performed in a common apparatus in any desired order in series and/or in parallel.

Figure 1